Transition metal ions in semiconductors: LDA, LDA+U, and experiment

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The known failure of the Local Density Approximation (LDA) is the underestimation of the band gap in solids, ascribed to the oversimplified treatment of exchangecorrelation effects, and particularly drastic in transition metal (TM) oxides. A considerable improvement is obtained by adding the +U correction for particular atomic orbitals. While the impact of +U terms was extensively discussed for ideal crystals, its impact on the electronic structure of defects is less understood. We analysed the impact of the +U term for Cr, Mn, Fe, and Co ions in GaN and AlN. The +U term was treated as a free parameter, and it was applied to p(N) and d(TM) orbitals. The results of LDA+U calculations were compared to available experimental data. The band gap of GaN is correct with U(N)=4 eV. The +U terms strongly affect the electronic structure of TM impurities. Surprisingly, for U(TM)=0, the energies of the gap levels induced by these centers, and of the intra-center optical transitions, agree well with experiment. In contrast, for U(N)=U(TM)=4 eV, these energies are in substantial disagreement with experimental values by about 1-2 eV.

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